

ABSTRACT OF THE DISCLOSURE

A method for producing endohedral fullerenes at a higher yield and an apparatus therefor are disclosed. The apparatus includes a vacuum vessel (1), elements (3, 4) for generating a plasma current (2) of atoms to be contained, elements (8) for introducing fullerenes into the plasma current (2), a holding member (6) for holding a plurality of division plates (5a, 5b, 5c) concentrically divided and arranged in the downstream region of the plasma current (2), and a bias-applying unit (7a, 7b, 7c) for applying an arbitrary bias voltage to the division plates (5a, 5b, 5c).